

*JFW*

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q77191

Koichi OHTO, et al.

Appln. No.: 10/650,193

Group Art Unit: 2826

Confirmation No.: 6245

Examiner: Alexander O. WILLIAMS

Filed: August 28, 2003

For: SEMICONDUCTOR DEVICE HAVING SILICON-DIFFUSED METAL WIRING  
LAYER AND ITS MANUFACTURING METHOD

**PETITION FOR EXTENSION OF TIME UNDER 37 C.F.R. § 1.136**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. § 1.136, Applicant hereby petitions for an extension of time of one (1) month, extending the time for responding to the Office Action of November 3, 2004 to March 3, 2005.

A check for the statutory fee of \$120.00 is attached. The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account. A duplicate copy of this sheet is enclosed.

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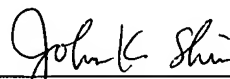
SUGHRUE MION, PLLC  
Telephone: (202) 293-7060  
Facsimile: (202) 293-7860

WASHINGTON OFFICE

**23373**

CUSTOMER NUMBER

Respectfully submitted,

  
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John K. Shin  
Registration No. 48,409

Date: March 2, 2005